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(54) Title: CHEMICALLY AMPLIFIED RESIST COMPOSITION AND METHOD FOR MANUFACTURING RESIST FILM
USING THE SAME

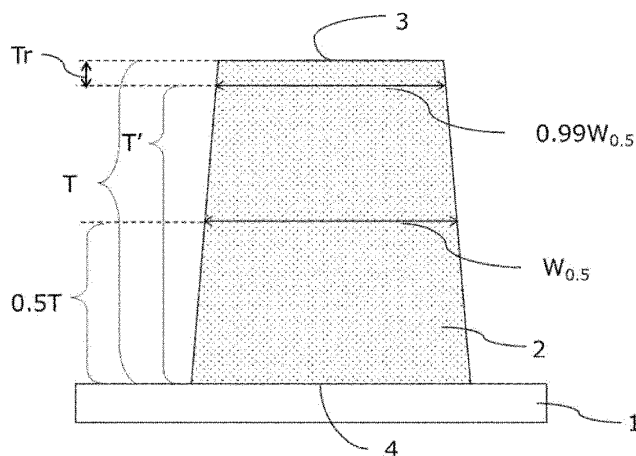


Figure 1

(57) Abstract: To provide a chemically amplified resist composition capable of forming a resist pattern having high rectangularity. A chemically amplified resist composition comprising an alkali-soluble resin (A) having a certain structure and a cLogP of 2.76 to 3.35, a photoacid generator (B), and a solvent (C).



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